



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Huey-Chiang Liou et al. § Group Art Unit: 2823
Serial No.: 10/695,103 §
Filed: October 28, 2003 §
For: Langmuir-Blodgett Chemically § Examiner: Trung Q. Dang
Amplified Photoresist §
Customer No.: 21906 § Atty. Dkt. No.: ITL.1054US
No.: § (P17790) §
§ Confirmation No.: 4735

Mail Stop-Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Applicant submits the references listed on the attached form PTO 1449 together with any required copies of such references.

This statement is being filed after a first Office action on the merits, but before receipt of a final Office action, a Notice of Allowance or an action that otherwise closes prosecution in the application. A check for \$180 in payment of the late submission fee of §1.17(p) is enclosed. Please apply any additional charges or credits to Deposit Account No. 20-1504(ITL.1054US).

Respectfully submitted,



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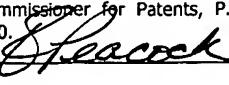
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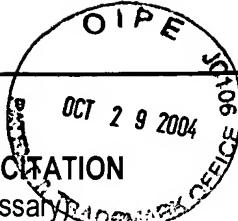
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INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)		ATTY DOCKET NO. ITL.1054US(P17790)	SERIAL NO. 10/695,103
		APPLICANT(S): Huey-Chiang Liou et al.	
		FILING DATE: October 28, 2003	GROUP ART UNIT: 2823

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
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FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
	AJ						
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	AO						
	AP						

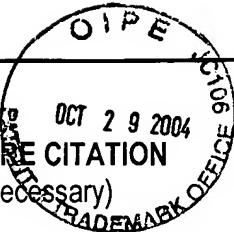
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

AQ	S. Elhadj, J. W. Woody, V. S. Niu and R. F. Saraf, <i>Orientation of self-assembled block copolymer cylinders perpendicular to electric field in mesoscale film</i> , Applied Physics Letters, vol. 82, no. 6, 10 Feb. 2003, p. 871-3.
AR	Huiwen Liu, Bharat Bhushan, <i>Orientation and relocation of biphenyl thiol self-assembled monolayers under sliding</i> , Ultramicroscopy, vol. 91, no. 1-4, May 2002, p. 177-83.
AS	Sang Jung Ahn, Yun Kyeong Jang, Haeseong Lee, and Haiwon Lee, <i>Mechanism of atomic force microscopy anodization lithography on a mixed Langmuir-Blodgette resist of palmitic acid and hexadecylamine on silicon</i> , Applied Physics Letters, vol. 80, no. 14, 8 April 2002, p. 2592-4.
AT	Tiesheng Li, Masaya Mitsuishi, and Tokuji Miyashita, <i>Photodegradable polymer LB films for nano-lithographic imaging techniques</i> , Thin Solid Films, vol. 389, no. 1-2, 15 June 2001, p. 267-71.

EXAMINE

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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BA	N.G. Semaltianos, H. Araujo, and E.G. Wilson, <i>Polymerization of Langmuir-Blodgett films of diacetylenes</i> , Surface Science, vol. 460, no. 1-3, 20 July 2000, p. 182-9.		
BB	Hiroyuki Sugimura, Atsushi Hozumi and Osamu Takai, <i>Fabrication of Coplanar Microstructures Composed of Multiple Organosilane Self-Assembled Monolayers</i> , IEICE Transactions on Electronics, vol. E83-C, no. 7, July 2000, p. 1099-103.		
BC	M. Sundermann, J. Hartwich, K. Rott, D. Meyners, E. Majkova, U. Kleineberg, M. Grunze, U. Heinzmann, <i>Nanopatterning of Au absorber films on Mo/Si EUV multilayer mirrors by STM lithography in self-assembled monolayers</i> , Surface Science, vol. 454-456, 20 May 2000, p. 1104-9.		
BD	Richard D. Peters, Xiao M. Yang, Tae K. Kim, B. H. Sohn, and Paul F. Nealey, <i>Using Self-Assembled Monolayers Exposed to X-rays To Control the Wetting Behavior of Thin Films of Diblock Copolymers</i> , Langmuir, vol. 16, no. 10, 16 May 2000, p. 4625-31.		
BE	Hiroyuki Sugimura, Kazuya Ushiyama, Atsushi Hozumi, and Osamu Takai, <i>Micropatterning of Alkyl- and Fluoroalkylsilane Self-Assembled Monolayers Using Vacuum Ultraviolet Light</i> , Langmuir, vol. 16, no. 3, 8 Feb. 2000, p. 885-8.		
BF	Hiroyuki Maruyama, Nobuyuki Kosai, Tadatake Sato, Shigehito Sagisaka, Hiroshi Segawa, Takeo Shimidzu and Kazuyoshi Tanaka, <i>Nanometer-Scale Lithography on the Oligosilane Langmuir-Blodgett Film</i> , Japanese Journal of Applied Physics, Part 1, vol. 36, no. 12A, Dec. 1997, p. 7312-16.		
BG	Chang Nam Kim, Dong Woo Kang, Eung Ryul Kim, and Haiwon Lee, <i>Fabrication of a Polymethylphenylmethacrylate Resist by Using Electron Beam Lithography</i> , Journal of the Korean Physical Society, vol. 31, no. 1, July 1997, p. 154-7.		
BH	T. Sato, and H. Ahmed, <i>Observation of a Coulomb staircase in electron transport through a molecularly linked chain of gold colloidal particles</i> , Applied Physics Letters, vol. 70, no. 20, 19 May 1997, p. 2759-61.		
BI	Earl T. Ada, Luke Hanley, Sergei Etchin, John Melngailis, Walter J. Dressick, Mu-San Chen and Jeffrey M. Calvert, <i>Ion beam modification and patterning of organosilane self-assembled monolayers</i> , Journal of Vacuum Science & Technology B, vol. 13, no. 6, Nov.-Dec. 1995, p. 2189-96.		
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